

# BONN DMAPS DEVELOPMENTS

FABIAN HÜGGING ON BEHALF OF THE BONN CMOS TEAM





TJ-Monopix2:

- 180 nm TowerSemi CMOS technology
- Small collection electrode
- 2x2 cm<sup>2</sup> matrix with **33x33 μm<sup>2</sup>** pixel pitch
- Substrate resistivity >1 k $\Omega$ cm



LF-Monopix2:

- 150 nm LFoundry CMOS technology
- Large collection electrode
- 2x1 cm<sup>2</sup> matrix with **50x150 μm<sup>2</sup>** pixel pitch
- Substrate resistivity > 2 k $\Omega$ cm

Same fast column drain readout architecture (FE-I3 like)







- Latest iteration TJ-Monopix2: 33.04 µm pixel pitch in 512 x 512 pixel matrix (2 x 2 cm<sup>2</sup>) — - 7 bit TOT resolution (40 MHz BCID clock - 25 ns timing)
- 3 bit in-pixel threshold tuning \_
- Communication via four differential lines
- Command-based slow control (taken from RD53B) —
- 160 MHz data output rate (frame-based 8b10b encoding) —
- bdaq53 readout board (from RD53A/B testing)







- Lab tests conducted for threshold and noise measurements
- Design goals: operational threshold  $\approx$  100 e<sup>-</sup>, threshold dispersion < 10 e<sup>-</sup>, ENC  $\approx$  5 e<sup>-</sup>
- In-pixel threshold trimming (3 bit) significantly reduces threshold dispersion to less than design value \_
- Operational threshold higher than anticipated, but we will see later that it should not be a problem



## **TJ-MONOPIX2 LAB TESTS**







- Noise (ENC) measured from steepness of S-curve when injecting varying charges
- Mean noise 5.6 e<sup>-</sup> in accordance with design goal \_
- No RTS noise tail observed as in TJ-Monopix1 \_
- Allows operation at low thresholds thanks to large S/N ratio
- Reminder: in TJ-Monopix1, operational threshold was O(400 e<sup>-</sup>) which lead to efficiency losses in pixel corners, especially after irradiation







- In-pixel efficiency for standard pixel flavor
- Homogeneous efficiency > 99 % with no losses in the corners, higher than TJ-Monopix1 already
- deviation within error (estimated around 0.1%)

Epi gap in n-layer (30 μm): 99.96 %



– With ~200 e<sup>-</sup> threshold no difference between samples expected for the observed cluster charge,

Cz gap in n-layer (100 μm): 99.72 %







- Compare different sensor materials (epi 30 µm / Cz 100 µm) regarding cluster size
- As expected from accumulated charge and higher depletion than 30 µm cluster size is significantly larger in 100 µm silicon (not fully depleted)



- High (average) cluster size allows for high spatial resolution; better than  $\frac{d}{\sqrt{12}}$  in Cz chip





- Beam tests performed at DESY (10/2023)
- Measure time between scintillator hit and HITOR word from in-pixel discriminator
- Delay gradient along column due to signal propagation -> correct by column-wise line fit
- Trigger delay of cluster vs. seed charge (outliers due to mismatch of delay to proper hit)







- Measure delay between scintillator and HitOr signal with 640 MHz clock
- Estimate in-time ratio of hits in given time window of trigger distance distribution
- For 30 µm epi chip with **n-gap** modification and standard front-end:
  - 99.68 % within 25 ns (ATLAS BX frequency)
  - > 99 % for 20 ns and 15 ns
- Estimate 99.64 % in-time efficiency based on in-time ratio and hit detection efficiency (analysis ongoing)









- Full scale column length with column-drain R/O
- Full in-pixel electronics while reducing the pixel pitch **by 40%** of predecessor
- 6 bit ToT information @ 25 ns
- **4 bit in-pixel threshold tuning**
- 6 front-end variations available
- Differing in CSA, feedback capacitance, tuning
- Successfully thinned down to **100 µm thickness and** backside processed
- Proton irradiated sensors up to 2e15 neq/cm<sup>2</sup> NIEL damage available
- Powered off during irradiation, annealed 80min @ 60°C

# **LF-MONOPIX2 SPECIFICATIONS**





![](_page_9_Picture_16.jpeg)

![](_page_10_Picture_0.jpeg)

- Measure leakage current per pixel at -20 °C environmental temperature
- Breakdown at approx. 460 V for unirradiated modules
- **Increase** in leakage current **per pixel 0.5 nA** per 1e15 neq/cm<sup>2</sup> irradiation step
- Extract gain from linear regression of untuned threshold at different global THR settings
- Smaller feedback capacitance  $\rightarrow$  larger gain (and faster rise time of LE)

![](_page_10_Figure_6.jpeg)

![](_page_10_Figure_10.jpeg)

![](_page_10_Picture_12.jpeg)

![](_page_11_Picture_0.jpeg)

- Controlled laboratory environment at -20°C
- Homogeneous threshold across matrix at approx. 2 ke<sup>-</sup> threshold before and after irradiation
  - About 40% increase in ENC after each 1e15 neq/cm<sup>2</sup> fluence step
- Expected charge MPV of MIP at full depletion 6 ke<sup>-</sup>

![](_page_11_Figure_5.jpeg)

![](_page_11_Picture_12.jpeg)

## L 0.068

- 0.120
- 0.137
- 0.154
- 0.189
- 0.206

![](_page_12_Picture_0.jpeg)

- Get calibrated charge MPV from Landau shaped beam spectrum (5 GeV electrons at DESY)
- Necessary voltage for full depletion increases from 15 V before to >100 V after irradiation to 1e15 neq/ cm<sup>2</sup>
- Large biasing capability enables full depletion even after 2e15 neq/cm<sup>2</sup> of fluence ToT beam spectrum

![](_page_12_Figure_4.jpeg)

![](_page_12_Figure_8.jpeg)

![](_page_12_Picture_10.jpeg)

![](_page_12_Picture_11.jpeg)

![](_page_13_Picture_0.jpeg)

- Mostly uniform in-time efficiency (25 ns) across matrix @ 1e15 neq/cm<sup>2</sup>
  - Measured at 2 ke<sup>-</sup> threshold and 150 V bias (fully depleted)
- Slight drop to 97.79 % in pixel corners
- Verified decrease in efficiency for lower bias voltages  $\rightarrow$  Less collected charge

![](_page_13_Figure_5.jpeg)

# **HIT DETECTION EFFICIENCY STUDIES**

![](_page_13_Figure_12.jpeg)

![](_page_13_Picture_14.jpeg)

![](_page_14_Picture_0.jpeg)

- Hit detection and in-time efficiencies > 99% for all matrices after irradiation to 1e15 n<sub>eq</sub> cm<sup>-2</sup>
- Measured at **2 ke<sup>-</sup> threshold** and 150 V bias voltage (full depletion)
- Increase in in-time ratio for larger gain front-end variants
- Result **before irradiation** as reference
- Similar threshold of ~2 ke<sup>-</sup>
- 60 V bias voltage (full depletion)
- $\rightarrow$  No significant efficiency loss after irradiation to 1e15 neq/cm<sup>2</sup> Detailed analysis of results after 2e15 neq/cm<sup>2</sup> ongoing

# **HIT DETECTION EFFICIENCY STUDIES**

![](_page_14_Figure_12.jpeg)

![](_page_14_Picture_14.jpeg)

![](_page_14_Picture_15.jpeg)

![](_page_15_Picture_0.jpeg)

- Two fully working DMAPS with column-drain readout in 2 cm long columns
- TJ-Monopix2:
  - Hit detection efficiency > 99 % for non-irradiated chips across front-end and substrate variants
  - In-time ratio (within 25 ns) > 99 %
- LF-Monopix2:
  - More than 99% in-time efficiency after irradiation to 1e15 n<sub>eq</sub> cm<sup>-2</sup>
  - Promising results for 2e15 n<sub>eq</sub> cm<sup>-2</sup> samples, analysis ongoing

The measurements leading to these results have been performed at the Test Beam Facility at DESY Hamburg (Germany), a member of the Helmholtz Association (HGF).

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![](_page_15_Picture_17.jpeg)

![](_page_15_Picture_18.jpeg)

![](_page_16_Picture_0.jpeg)

# BACKUP

![](_page_17_Picture_0.jpeg)

![](_page_17_Figure_1.jpeg)

✓ Optimized individual parts ✓ High rad. tolerance

X Cost and labor intensive bump-bonding

![](_page_17_Figure_4.jpeg)

Reduced material budget ✓ Commercial processes: Fast & high volume

- production
- Lower module cost

X Sensor not fully depleted Not radiation hard

# DEPLETED MONOLITHIC ACTIVE PIXEL SENSOR

![](_page_17_Figure_15.jpeg)

- CMOS processes offer high-resistivity substrate
- Bias voltage capabilities (HV)

✓ Strong drift field Enhanced charge collection  $\rightarrow$  Increased radiation tolerance

![](_page_17_Picture_20.jpeg)

![](_page_18_Picture_0.jpeg)

- TJ-Monopix is line of DMAPS designed in a 180 nm Tower CMOS process based on ALPIDE sensor for ALICE ITS upgrade
- Small collection electrode for operations with low power and low noise
- Designed for ATLAS ITk outer layer specs with column-drain readout like in FE-I3 in a 2 cm column
- Pixel readout capable of dealing with hit rate > 100 MHz / cm<sup>2</sup>
- Goal: 10<sup>15</sup> 1 MeV <sup>neq</sup>/<sub>cm2</sub> NIEL tolerance and 100 MRad TID
- Low dose n-type implant for homogeneous depletion of sensor volume (initial design)
- Radiation hardness not straight-forward in small collection electrode design

# **TJ-MONOPIX DESIGN**

![](_page_18_Figure_11.jpeg)

![](_page_18_Picture_12.jpeg)

![](_page_19_Picture_0.jpeg)

- Extensive tests performed in 2018 at ELSA beam line (2.5 GeV electrons) in Bonn
- Significant efficiency loss after irradiation to < 70 % (at  $10^{15}$  neq cm<sup>-2</sup>)
- Charge is lost due to E-field shaping under deep pwell -> need another modification besides low dose n-type

![](_page_19_Figure_4.jpeg)

# **RADIATION HARDNESS TJ-MONOPIX1**

![](_page_19_Picture_8.jpeg)

![](_page_19_Picture_9.jpeg)

![](_page_20_Picture_0.jpeg)

- Low electric field below deep p-well in
- well) below readout electronics to shape electrical field towards collection node

![](_page_20_Picture_3.jpeg)

![](_page_20_Picture_4.jpeg)

## **IMPROVED SENSOR DESIGN**

![](_page_20_Picture_9.jpeg)

![](_page_21_Picture_0.jpeg)

- Measured  $10^{15}$  neq cm<sup>-2</sup> irradiated chips in 5 GeV electron beam at DESY
- Efficiency improvement in epi chip from 69 % to 87 % due to sensor modifications \_\_\_\_
- More sensitive volume and more charge in Cz leads to full efficiency after irradiation \_

![](_page_21_Figure_4.jpeg)

## **RADIATION HARDNESS NEW DESIGN**

![](_page_21_Figure_8.jpeg)

300 µm Cz: 98.6 % @ 490 e-

![](_page_21_Picture_11.jpeg)

![](_page_22_Picture_0.jpeg)

- Threshold in TJ-Monopix1 mostly limited by unexpectedly high noise
- Tail identified as RTS noise

![](_page_22_Figure_4.jpeg)

## - Enlarged transistors for smaller noise and threshold (tested in miniMALTA before TJ-Monopix2 (CERN))

![](_page_22_Figure_10.jpeg)

![](_page_22_Picture_12.jpeg)

![](_page_22_Picture_13.jpeg)

![](_page_23_Picture_0.jpeg)

- Investigated samples (unirradiated): \_\_\_\_
  - epitaxial silicon (30 µm thickness) with gap in n-layer —
  - Czochralski silicon (100 µm thickness) with gap in n-layer \_
  - —
- All samples operating at a threshold of ~200 e<sup>-</sup>

![](_page_23_Figure_7.jpeg)

# **TJ-MONOPIX2 BEAM TESTS**

Beam tests performed at DESY in November 2022 (5 GeV electron beam, Mimosa26 telescope)

Type of silicon growth (epi vs Cz) not part of investigation, but thickness of sensitive volume

![](_page_23_Picture_13.jpeg)

![](_page_23_Picture_15.jpeg)

![](_page_24_Picture_0.jpeg)

- Cluster charge (MPV) for standard pixel flavor
- Cz sample has higher MPV since depletion is not limited by thickness of epi layer (30 μm)
- Still not fully depleted because of -6 V bias voltage on substrate and p-wells on top of chip

![](_page_24_Figure_4.jpeg)

![](_page_24_Figure_9.jpeg)

![](_page_24_Picture_12.jpeg)

![](_page_25_Picture_0.jpeg)

- \_ allows for lower thresholds
- M6 is coupling capacitor, area increased by factor 7.5 for better coupling to GN node (gain stage input)
- Impedance matching M1 (output) to M2 (input)
- ENC reduced by factor 2 (by simulation)
- Gain at threshold increased by factor 3 (again sim)

## **TJ-MONOPIX2 FRONT-END**

## Increased size of M1 (and also M6) increases the gain and effectively decreases ENC which in turn

![](_page_25_Figure_10.jpeg)

![](_page_25_Picture_12.jpeg)

![](_page_25_Picture_13.jpeg)

![](_page_26_Picture_0.jpeg)

- DAQ System based on RD53A/B readout board bdaq53
- Standalone carrier PCB with power and DisplayPort connector
- Readout board with 1 Gbit/s connection to DAQ computer (10) Gbit/s possible)
- Small and portable setup for irradiations, beam tests etc.
- Chip supports addressing by chip ID (jumper on pin header)
  - Multi-chip readout should be possible with bdaq53

![](_page_26_Picture_7.jpeg)

![](_page_26_Picture_13.jpeg)

![](_page_26_Picture_14.jpeg)

![](_page_26_Picture_15.jpeg)

![](_page_27_Picture_0.jpeg)

CSA 1 NMOS amplifier from LF-Monopix1

![](_page_27_Figure_3.jpeg)

## CSA 2 Telescopic cascaded structure

## CSA 3

Current into input transistor from two separately adjustable branches

![](_page_27_Picture_11.jpeg)

![](_page_27_Picture_12.jpeg)

![](_page_28_Picture_0.jpeg)

## Unidirectional Self-biased differential amplifier followed by a CMOS inverter

![](_page_28_Figure_2.jpeg)

## **Bidirectional**

Optimized transistor dimensions and swapped input ports for faster speed

![](_page_28_Figure_8.jpeg)

![](_page_28_Picture_10.jpeg)

![](_page_28_Picture_11.jpeg)

![](_page_29_Picture_0.jpeg)

- Derived from ATLAS FE-I3 readout chip
- Rate capabilities around 100 MHz/cm<sup>2</sup>
- Token propagation along column \_
- Readout controller at end of column (READ, FREEZE to pixels)
- Data propagated along column with row \_ address, leading edge and trailing edge
- Periphery merges data from one TOKEN signal into frames that are transmitted 8b10b encoded to readout board

![](_page_29_Figure_7.jpeg)

# **COLUMN DRAIN READOUT**

![](_page_29_Picture_12.jpeg)

![](_page_30_Picture_0.jpeg)

	ALICE LHC	
		Οι
Time resolution [ns]	20 000	
Particle rate [kHz / mm <sup>2</sup> ]	10	10
Fluence [neq cm <sup>-2</sup> ]	> 1013	1
lon. Dose [MRad]	0.7	Ę

- rad-hard DMAPS

![](_page_30_Figure_7.jpeg)

Design specification for

DMAPS potential candidate

![](_page_30_Picture_12.jpeg)

![](_page_30_Picture_13.jpeg)